

L Number	Hits	Search Text	DB	Time stamp
-	508969	rough\$5 or haze	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:34
-	922010	hydrogen or "h.sub.2"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/21 10:05
-	397567	hcl or hydro\$1chloric or (hydrogen adj3 chlori?e)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/21 10:05
-	112606	epitax\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/21 10:05
-	2960705	semiconductor or si or silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:36
-	86606	(light adj3 scatter\$4) or lls or (defect adj3 density)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:01
-	2047834	wafer or substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:37
-	1426817	polish\$5 or grind\$4 or ground	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:38
-	71829	epitax\$5 with (wafer or substrate )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:39
-	62786	(epitax\$5 with (wafer or substrate )) and (semiconductor or si or silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:39
-	1559	((epitax\$5 with (wafer or substrate )) and (semiconductor or si or silicon)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (polish\$5 or grind\$4 or ground )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 12:41
-	385	((epitax\$5 with (wafer or substrate )) and (semiconductor or si or silicon)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (polish\$5 or grind\$4 or ground )) and ((light adj3 scatter\$4) or lls or (defect adj3 density) )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 15:58
-	9274	cop or (crystal\$6 adj4 originat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:00

-	36961	lpd or (light adj3 point)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:00
-	90857	light near4 scatter\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:01
-	6917	stock\$3 adj5 (remov\$4 or polish\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:03
-	130838	(cop or (crystal\$6 adj4 originat\$4)) or (lpd or (light adj3 point)) or (light near4 scatter\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:03
-	57	((cop or (crystal\$6 adj4 originat\$4)) or (lpd or (light adj3 point)) or (light near4 scatter\$4)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (stock\$3 adj5 (remov\$4 or polish\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:50
-	3560	((cop or (crystal\$6 adj4 originat\$4)) or (lpd or (light adj3 point)) or (light near4 scatter\$4)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (semiconductor or si or silicon) and (wafer or substrate )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:52
-	528	((cop or (crystal\$6 adj4 originat\$4)) or (lpd or (light adj3 point)) or (light near4 scatter\$4)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (semiconductor or si or silicon) and (wafer or substrate )) and epitax\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:52
-	361	((cop or (crystal\$6 adj4 originat\$4)) or (lpd or (light adj3 point)) or (light near4 scatter\$4)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (semiconductor or si or silicon) and (wafer or substrate )) and epitax\$5 not (((epitax\$5 with (wafer or substrate )) and (semiconductor or si or silicon)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (polish\$5 or grind\$4 or ground )) and ((light adj3 scatter\$4) or lls or (defect adj3 density) ))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 16:59
-	367	((cop or (crystal\$6 adj4 originat\$4)) or (lpd or (light adj3 point)) or (light near4 scatter\$4)) and (rough\$5 or haze) and ((hydrogen or "h.sub.2") or (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e))) and (semiconductor or si or silicon) and (wafer or substrate )) and epitax\$5 and (polish\$5 or grind\$4 or ground )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 17:11
-	2	("6284384").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/19 17:55

-	1703	(438/478 or 438/492 or 438/503 or 438/974).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/10/21 10:04
-	397988	hcl or hydro\$1chloric or (hydrogen adj3 chlori?e)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/10/21 10:05
-	922651	hydrogen or "h.sub.2"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/10/21 10:05
-	112707	epitax\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/10/21 10:06
-	112	((438/478 or 438/492 or 438/503 or 438/974).ccls.) and (hcl or hydro\$1chloric or (hydrogen adj3 chlori?e) ) and (hydrogen or "h.sub.2" ) and epitax\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/10/21 10:06